

Title (en)

# YIG THIN FILM MICROWAVE APPARATUS

Publication

**EP 0208548 A3 19880727 (EN)**

Application

**EP 86305294 A 19860709**

Priority

- JP 4320686 A 19860228
- JP 15043085 A 19850709

Abstract (en)

[origin: EP0208548A2] Microwave apparatus includes a YIG thin film device (1) utilising the ferrimagnetic resonance effect, and a magnetic circuit (2) having a gap of length  $l_g$  in which the YIG thin film device is provided and applying a bias magnetic field perpendicular to a film surface of the YIG thin film device, the magnetic circuit (2) including a permanent magnet (4) having a thickness  $l_m$  and a soft magnetic plate (5) having a thickness  $l_x$ . <??>The permanent magnet (4) satisfies the characteristics <MATH> and the soft magnetic plate satisfies the characteristics <MATH> wherein:  $f_0$  is the resonance frequency of the YIG thin film device (1);  $\gamma$  is the gyromagnetic ratio of the YIG thin film;  $NZ<Y>$  is the demagnetisation factor of the YIG thin film;  $4\pi M_{so}<Y>$  is the saturation magnetisation of the YIG thin film at room temperature;  $4\pi M_{so}<Y>$  is the saturation magnetisation of the soft magnetic plate (5);  $B_r$  DEG is the remanence of the permanent magnet (4) at room temperature;  $\alpha_1<B>$  is the first order temperature coefficient of the remanence of the permanent magnet (4) at or near room temperature;  $\alpha_1<Y>$  is the first order temperature coefficient of the saturation magnetisation of the YIG thin film at or near room temperature; and  $\alpha_1<x>$  is the first order temperature coefficient of the saturation magnetisation of the soft magnetic plate (5) at or near room temperature. <??>The thicknesses  $l_m$  and  $l_x$  are selected to improve the temperature dependency of the resonance frequency of the apparatus, such that it is capable of operating stably over wide ranges of working frequencies and temperatures.

IPC 1-7

**H01P 1/218; H01F 10/24**

IPC 8 full level

**H01F 10/24** (2006.01); **H01P 1/218** (2006.01)

CPC (source: EP KR US)

**H01F 10/245** (2013.01 - EP US); **H01P 1/218** (2013.01 - EP US); **H03B 9/00** (2013.01 - KR)

Citation (search report)

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